



ATTY. DOCKET NO. SERIAL NO. INFORMATION DISCLOSURE 55071-131 10/083,683 CITATION IN AN APPLICATION APPLICANT Xuelong SHI, et al. FILING DATE **GROUP** (PTO-1449) 2825 February 27, 2002 U.S. PATENT DOCUMENTS FILING DATE EXAMINER'S PATENT NO. DATE NAME **CLASS SUBCLASS INITIALS** 5,229,872 7/20/1993 Mumola 359 40 9/7/1993 Chen et al. 430 5 5,242,770 3/22/1994 Vogt et al. 5,296,891 355 67 8 2003 6/4/1996 Nelson 5,523,193 430 311 Loopstra et al. 5.969,441 10/19/1999 12 310 Van Der Werf et al. *5*3 4/4/2000 355 6,046,792 FOREIGN PATENT DOCUMENTS Translation EXAMINER'S CLASS SUBCLASS DATE COUNTRY **INITIALS** PATENT NO. WIPO (PCT/IB98/00254) WO 9/17/1998 WP 98/40791 ABSTRACT OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.) E. Wolf, "Electromagnetic diffraction inoptical systems, I. An integral representation of the image field", Department of Theoretical Physics, University of Manchester, pp. 349-356, dated 1859 Michael S. Yeung et al., "Extension of the Hopkins theory of partially coherent imaging to include thin-film interference effects, SPIE Vol. 1927 Optical/Laser Microlithography VI (1993), pp. 452-463. Donis G. Flagello et al., "Theory of high-NA imaging in homogeneous thin films", 1996 Optical Society of America, pp. 53-64. J. Fung Chen et al., "An OPC Technology Roadmap to 0.14μm Design Rules", SPIE Vol. 3236, no date pp. 382-396. Robert Socha et al., "Forbidden Pitches for 130nm lithography and below", Proceedings of SPIE Vol. 4000 (2000), pp. 1140-4455. DATE CONSIDERED **EXAMINER** 10/2003